			in
	Application No.	Applicant(s)	11
Notice of Allowability	09/891,730	VERHAVERBEKE	ET AL.
	Examiner	Art Unit	
	Lynette T. Umez-Eronini	1765	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.315	(OR REMAINS) CLOSED in this a) or other appropriate communication (IGHTS. This application is subject	pplication. If not incluen will be mailed in du	uded ue course. THIS
1. This communication is responsive to <u>12/27/2004</u> .			
2. X The allowed claim(s) is/are <u>1, 3, 4, 6-13, 15-23, 41-51, 59-110 and 112</u> .	-66, 67-78, 79, 80-82, 83, 84-85, 86	S-87, 88-96, 100, 102,	104, 106, 109,
3. \boxtimes The drawings filed on <u>25 June 2001</u> are accepted by the E	Examiner.		
4. ☐ Acknowledgment is made of a claim for foreign priority u a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have	e been received.		
2. Certified copies of the priority documents have			
 Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)). 	ocuments have been received in this	s national stage appli	cation from the
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a reply MENT of this application.	y complying with the I	requirements
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which giv			NOTICE OF
 CORRECTED DRAWINGS (as "replacement sheets") mu (a) ☐ including changes required by the Notice of Draftsper 1) ☐ hereto or 2) ☐ to Paper No./Mail Date (b) ☐ including changes required by the attached Examiner Paper No./Mail Date 	son's Patent Drawing Review(PTC -	,	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	l.84(c)) should be written on the draw the header according to 37 CFR 1.121	rings in the front (not t l(d).	he back) of
 DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT 	osit of BIOLOGICAL MATERIAL FOR THE DEPOSIT OF BIOLOGIC	must be submitted CAL MATERIAL.	. Note the
Attachment(c)			
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5. Notice of Informal	Patent Application (P	TO-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Summar Paper No./Mail Da		
Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date			
Examiner's Comment Regarding Requirement for Deposit of Richards Metarial	8. 🛛 Examiner's Statem	nent of Reasons for A	llowance
of Biological Material	9. 🗌 Other	LANVE	VD-1
		PRIMARY EX	
		\sim $//$	

REASON FOR ALLOWANCE

1. Claims 1, 3, 4, 6-13,15-23, 41-51, 59-66, 67-78, 79, 80-82, 83, 84-85, 86-87, 88-96, 100, 102, 104, 106, 109, 110 and 112 are allowed.

As to claims 1, 3, 4, 6-13, and 15-23, the prior art of record taken alone or in combination fails to suggest, teach or render obvious a method of processing a wafer comprising: exposing a wafer to a solution comprising ethylenediaminediorthohydroxyphenylacetic acid (EDDHA) along with NH₄OH, H₂O₂, and H₂O, wherein said wafer is exposed to said solution in an approximate range of 30 and 90 seconds while spinning and applying acoustic waves to said wafer, in combination with the rest of the limitations of said claims;

As to claims 41-51, 59-66, 79-96, and 100; the prior art of record taken alone or in combination fails to suggest, teach or render obvious the sequence of steps in a method cleaning a wafer, in combination with the rest of the limitations of the said claims;

As to claims 67-78, the prior art of record taken alone or in combination, fails to suggest, teach, or render obvious a method of processing a wafer comprising the step of after placing a wafer in a single wafer cleaning tool, dispensing an HF solution on said wafer for 2-3 seconds to etch approximately 0.5 Å - 5Å of a thermal oxide on said wafer, along with the rest of the limitations of the said claims; and

As to claims 102; 104; 106, 109, and 110; and 112, the prior art of record, taken either alone or in combination, fails to disclose or render obvious a method of cleaning a

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wafer, respectively with N,N'-Bis(2-hydroxyphenyl)ethylenediiminodiacetic acid (HPED); trietyhlenetranitrilohexazcetic acid (TTHA); desferriferrrioxamin B.; and molybdic acid, in combination with the rest of the limitations of the above claims.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lynette T. Umez-Eronini whose telephone number is 571-272-1470. The examiner is normally unavailable on the First Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Art Unit 1765

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February 10, 2005

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